

L Number	Hits	Search Text	DB	Time stamp
1	639	((electron adj projection) or lithography) and (secondary adj electrons)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:39
2	47	((((electron adj projection) or lithography) and (secondary adj electrons)) and (electron adj emitter)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:40
3	37	(((((electron adj projection) or lithography) and (secondary adj electrons)) and (electron adj emitter)) and substrate	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:37
4	0	(((((electron adj projection) or lithography) and (secondary adj electrons)) and (electron adj emitter)) and substrate) and ((electron adj emitter) near4 opposite)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:40
5	33419	((electron adj projection) or lithography) and substrate	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:39
6	369	((electron adj projection) or lithography) and substrate) and (electron adj emitter)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:43
7	4	(((((electron adj projection) or lithography) and substrate) and (electron adj emitter)) and ((electron adj emitter) near4 opposite)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:43
8	12	(((((electron adj projection) or lithography) and substrate) and (electron adj emitter)) and (permanent adj magnet)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:44

L Number	Hits	Search Text	DB	Time stamp
1	3	"6476402"	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 14:35
-	639	((electron adj projection) or lithography) and (secondary adj electrons)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:39
-	47	((((electron adj projection) or lithography) and (secondary adj electrons)) and (electron adj emitter)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:40
-	37	(((((electron adj projection) or lithography) and (secondary adj electrons)) and (electron adj emitter)) and substrate	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:37
-	0	(((((electron adj projection) or lithography) and (secondary adj electrons)) and (electron adj emitter)) and substrate) and ((electron adj emitter) near4 opposite)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:40
-	33419	((electron adj projection) or lithography) and substrate	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:39
-	369	((((electron adj projection) or lithography) and substrate) and (electron adj emitter)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:43
-	4	(((((electron adj projection) or lithography) and substrate) and (electron adj emitter)) and ((electron adj emitter) near4 opposite)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:43
-	12	(((((electron adj projection) or lithography) and substrate) and (electron adj emitter)) and (permanent adj magnet)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:49